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AMAT Docket No. 2616 US/RTP/LE
BSTZ Docket No. 4887P090

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Guangcai Xing, et al.

Application No. 09/298,064

Filed: April 22, 1999

For: APPARATUS AND METHOD FOR
EXPOSING A SUBSTRATE TO PLASMA
RADICALS

Examiner: Zervigon, R.

Art Unit: 1763

BOX RCE
Assistant Commissioner for Patents
Washington, D.C. 20231

REQUEST FOR CONTINUED EXAMINATION

Pursuant to 37 C.F.R. § 1.114, Applicants respectfully request Continued Examination of the above-referenced application for consideration of an Information Disclosure Statement. An Information Disclosure Statement and the appropriate fee are submitted herewith.

In connection with the request for Continued Examination, Applicants submit for consideration a copy of the pending claims as well as the following remarks.

REMARKS

In an Office Action dated June 4, 2001, the Patent Office had finally rejected Claims 1-4, 6-7 and 17-20 under 35 U.S.C. § 102(b) and Claim 5 under 35 U.S.C. § 103(a). Reconsideration is respectfully requested.

A. 35 U.S.C. § 102(b): Rejection of Claims 1-4, 6 and 7

The Patent Office rejects Claims 1-4, 6 and 7 under 35 U.S.C. § 102(b) as anticipated by Matsuo.

Applicants reiterate that Matsuo does not describe nitrogen radicals that react with a substrate in a film conversion step. Regarding independent Claim 1, Matsuo does not describe an